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PATENT  
Customer No. 22,852  
Attorney Docket No. 07553.0009

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: )  
 )  
Michiaki SANO ) Group Art Unit: 1765  
 )  
Serial No.: 09/671,201 ) Examiner: L. Vinh  
 )  
Filed: September 28, 2000 )  
 )  
For: PLASMA PROCESSING )  
METHOD )

Assistant Commissioner for Patents  
Washington, DC 20231

Sir:

RECEIVED  
MAY 03 2002  
TC 1700

AMENDMENT

In reply to the Office Action dated January 9, 2002, the period for reply having been extended for one month by a request for extension and fee payment filed concurrently herewith, please amend the application as follows:

IN THE CLAIMS:

Please cancel claims 1-6 without prejudice or disclaimer, and add new claims 7-40, as follows:

7. (New) A plasma processing method for removing a photoresist film formed at a workpiece placed within a processing chamber, comprising:
- applying high-frequency power for biasing to the workpiece at a first power level;
- raising the processing gas to a plasma; and

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